

# Coventor Overview

# Company Overview

COVENTOR

## Coventor History:

Founded in 1996

Expertise in 3D modeling and simulation

Initially focused on tools for MEMS design

## Focus:

Provide 3D solutions to the MEMS and semiconductor industries that harness compute power to dramatically reduce physical prototyping

Privately Held

- Needham Capital
- Intel Capital



Headquarters — Cary, NC

Development centers

- Waltham, Massachusetts
- Paris, France

Global sales and support

# Leadership Team

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Highly experienced team,  
many **years at Coventor** and  
serving the MEMS industry



**Mike Jamiolkowski**  
President and CEO, Founder  
**18 years, founded ISS EDA company**



**David Fried, PhD**  
CTO, Semiconductor  
**2 years +  
14 years IBM**



**Steve Breit, PhD**  
VP, Engineering  
**14 years**



**Gerold Schropfer, PhD**  
Director, Europe and  
Foundry Program  
**13 years**



**Tom Flynn**  
VP, Worldwide Sales  
**4 years +  
14 years Ansoft**



**Ken Greiner**  
Director,  
SEMulator3D R&D  
**16 years**



**Gunar Lorenz, PhD**  
Director,  
*MEMS+* R&D  
**14 years**



**Matt Kamon, PhD**  
Principal Technologist,  
Simulation R&D  
**16 years**



**Chris Welham, PhD**  
Manager,  
Applications Eng.  
**15 years**

# Serving the World Leaders in MEMS and Semiconductors

COVENTOR

IDMs

Fabless Companies

Foundries & Others

MEMS



InvenSense

FAIRCHILD  
SEMICONDUCTOR

FAB  
MIXED-SIGNAL FOUNDRY EXPERTS

DALSA



Canon

RFMD

QUALCOMM



wolfson  
microelectronics

IDT

wiSpry  
Dynamically Tunable RF



Fraunhofer

OMRON

DENSO

mCube  
TESSERA

TOYOTA

HYUNDAI



STANFORD  
UNIVERSITY

LEXMARK

Honeywell

Medtronic

HYUNDAI

TriQuint  
SEMICONDUCTOR

NIST

EPSON  
EXCEED YOUR VISION

Theon  
sensors

FUJITSU FUJITSU LABORATORIES

BOEING

IBM

Micron

tsmc

GLOBAL  
FOUNDRIES

intel

SONY

infineon

KLA Tencor

imec

Seagate

WD

TOKYO ELECTRON

TOKYO ELECTRON

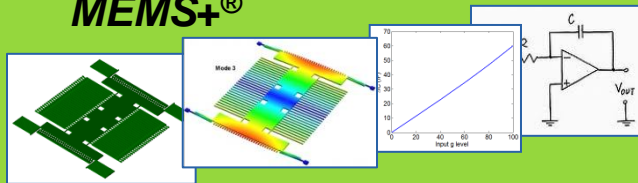
Semiconductor

Growing number of customers purchase both  
MEMS and semiconductor solutions from Coventor

# Our Product Platforms

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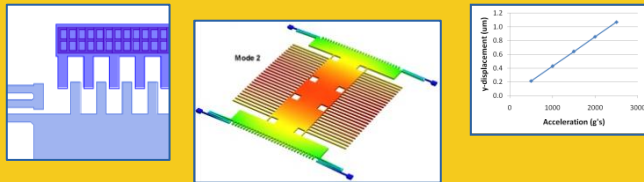
## MEMS+<sup>®</sup>



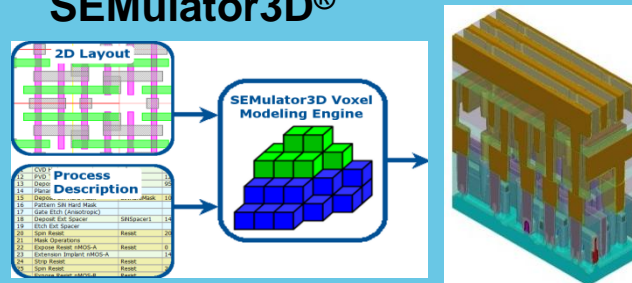
## MEMS Component Design and System Simulation

- Behavioral-level FEA for rapid concept exploration and optimization
- MEMS + IC system design
- Multi-physics FEA of highly non-linear, coupled electro-mechanical, fluidic, and thermal effects

## CoventorWare<sup>®</sup>



## SEMulator3D<sup>®</sup>



## Process Technology Development

- Virtual fabrication MEMS and semiconductor devices
- Predictive, silicon-accurate, 3D structures
- Uses include process development, process integration, physical verification, and technology transfer



# The Traditional Approach to MEMS Design

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## ASIC Design



Control System Design

Control System Design

Control System Design

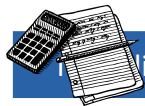
cadence®

IC Design

IC Design

IC Design

## MEMS Design



*Design-specific*

Modeling

Modeling

Modeling



Conventional FEA

Conventional FEA

Conventional FEA

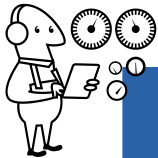
Conventional

*Too slow to inform fab cycles*

*Full coupling infeasible*

## Fab / Foundry

*Consequence: too many "build and test" cycles*



MEMS Process Learning Cycle

MEMS Process Learning Cycle

MEMS Process Learning Cycle

# MEMS+ is a New Approach

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## ASIC Design



Control System Design

cadence®

IC Design

*MEMS and IC co-design*

## MEMS Design



Modeling



MEMS+, A Different Kind of FEA

Conventional FEA

*Automatically generated, tunable accuracy vs. speed*

*Industrial strength,  
Fast AND Accurate,  
Full coupling feasible*

*Complementary, for details and verifying MEMS+*

*Rapid Design Studies  
Optimization  
Manufacturability*

## Fab / Foundry



MEMS Process  
Learning Cycle

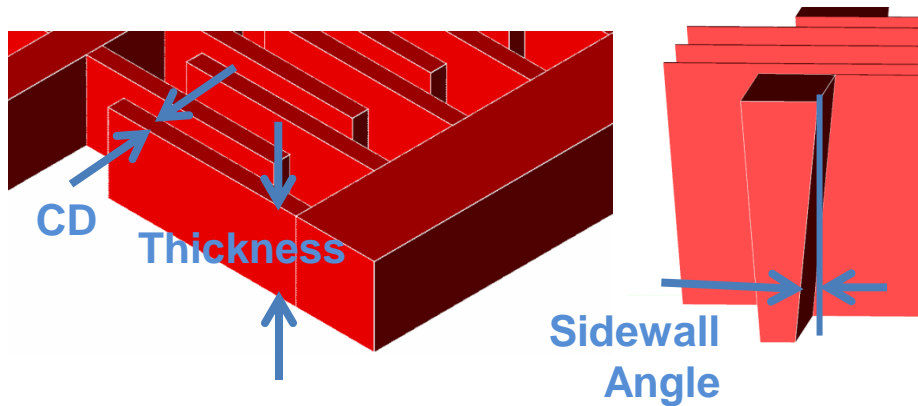
MEMS Process  
Learning Cycle

*Result: fewer “build and test” cycles*

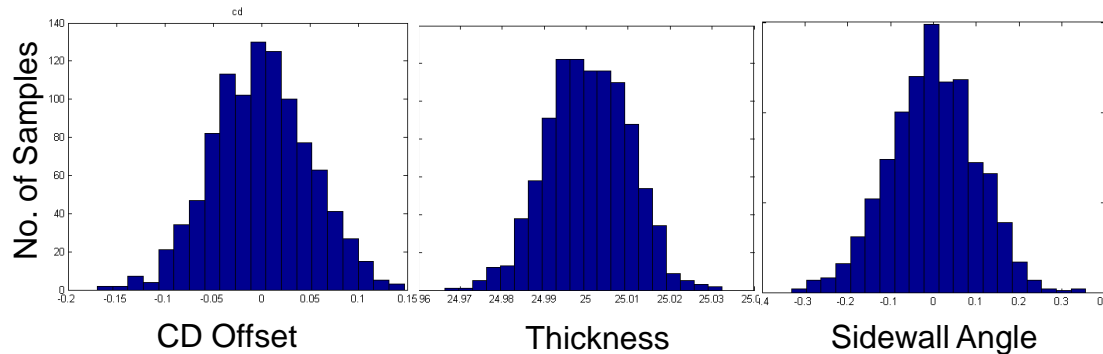
# MEMS+ Analysis of Manufacturing Sensitivity

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SOI MEMS process, 3 input variables

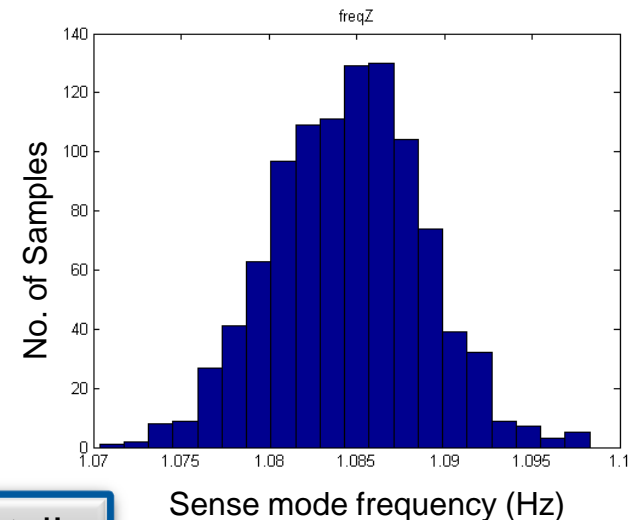
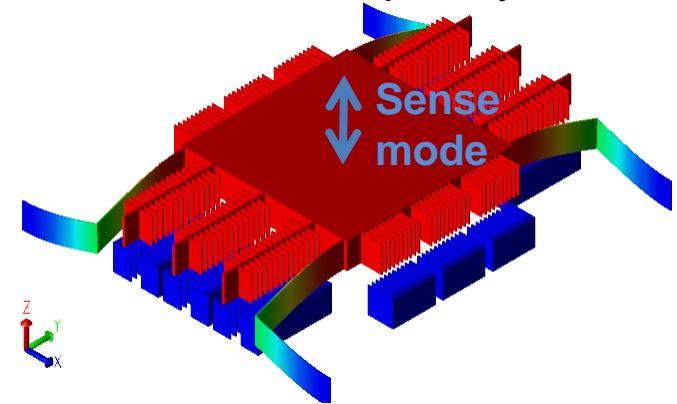


Monte Carlo study, 1000 samples



7 sec per sample, less than 2 hrs total!

Functional spec:  
sense mode frequency





# MEMS+ Reference - Murata

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Tero Sillanpää , Murata ASIC Design Manager:

“The Verilog-A Reduced Order Model (ROM) exported from *MEMS+* captures second-order effects not seen in basic hand-crafted models without any compromise in simulation performance. We were able to create a Verilog-A ROM of a complex gyro design in just a few minutes, allowing our ASIC team to work in parallel with the MEMS team on further design iterations. Transient simulations in Cadence showed that the model maintained the expected modal frequencies and was stable. The robust model exchange between MEMS and ASIC designers enabled by *MEMS+* reduces the probability of design error and can help avoid costly redesign iterations needed to address unexpected behavior.”



Accelerometers



Gyro/accelerometer  
combo sensors



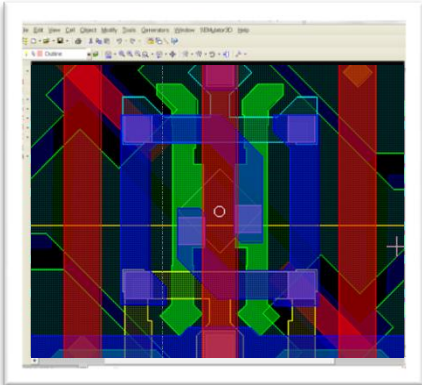
Pressure sensors



# What is SEMulator3D?

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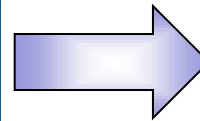
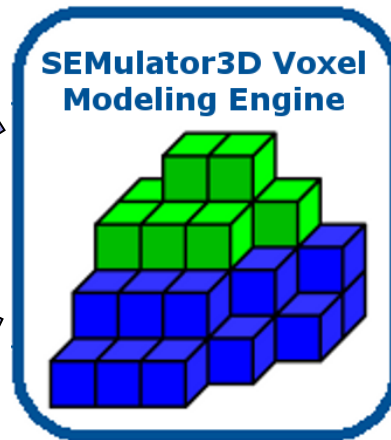
## A Powerful Virtual Fabrication Platform for MEMS and Semiconductors



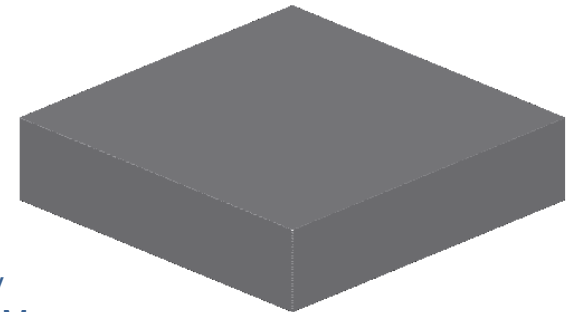
Layout Editor:  
Design, OPC,...

Step	Step Name	Material Name	Thickness	Mask Name	Depth	Mask
1	Simulation Setup	SiO2, BCN	100	buldbounds		
2	SiO2 Wafer Setup					
3	SiO2 Implant			Novell	50	
4	PECVD Module					
5	Gate Hard Mask					
5.1	High-K Gate Dielectric Deposition	HF02	2			
5.2	Measure Film Thickness					
5.3	PNIP TiN Deposition	TiN_PNIP	6			
5.4	Measure Film Thickness					
5.5	Barrier TiN Deposition	TiN	2			
5.6	SiO2 Resist Deposition	Resist	200			
5.7	SiO2 Lithography	Resist	400	Novell		
5.8	SiO2 TiN Removal Etch				25	
5.9	SiO2 Resist Strip	Resist				
5.10	SiO2 TiN Deposition	TiN_SiO2	10			
5.11	Gate Amorphous Silicon Deposition	Si_Amorph	200			
5.12	Gate Amorphous Silicon CMP					
5.13	Gate Hard Mask Deposition	Si3N4_PECVD	100			
5.14	Gate Patterning					
5.14.1	Gate Resist Deposition	Resist	200			
5.14.2	Gate Lithography			GateLitOut		
5.14.3	Pattern Gate Hard Mask	Resist	400			
5.14.4	Gate Resist Strip	Resist			100	
5.15	Measure CD					
5.16	GateCut Patterning					

Process Editor:  
Step-by-Step Process  
Behavioral Description



3D Viewer:  
MEMS display  
mirror on SRAM

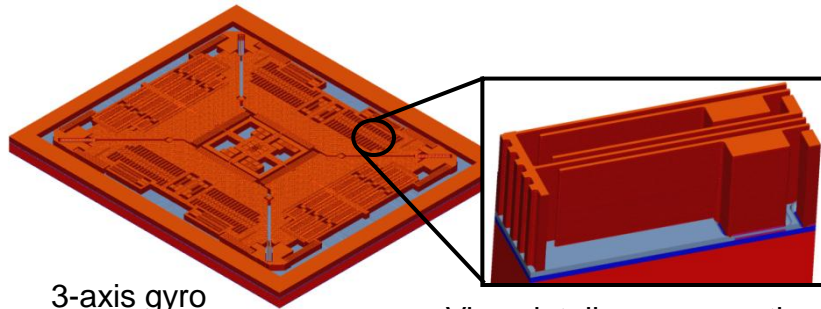


- Applicable to any process & any layout
- Handles complete process sequences and large areas
- Provides 3D structural models that are **accurate**, not idealized
- Provides **predictive** insights on design/technology interactions, saving "build-and-test" cycles

# Virtual Fabrication: Uses for MEMS

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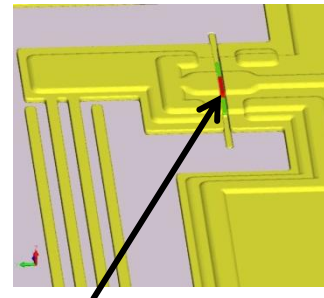
**Communication:** Visualize, Animate process,  
Designers  $\leftrightarrow$  Fab/Foundry, Tech transfer



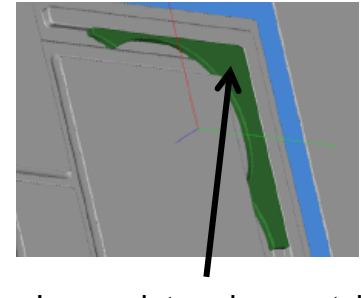
3-axis gyro  
from chipworks teardown

View details, cross section

**Physical Verification:** Check structures,  
release completion, electrical continuity

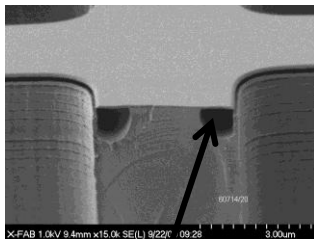


Design error passed 2D DRC

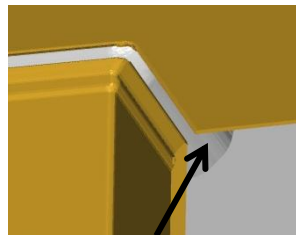


Incomplete release etch

**Process Development:** Predict/diagnose  
process problems

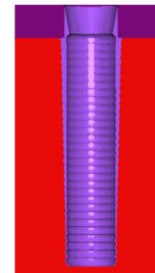


Issue: unexpected voids

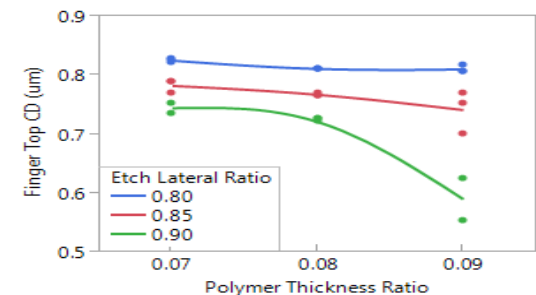


SEMulator3D model  
confirms root cause

**Yield Optimization:**



DRIE

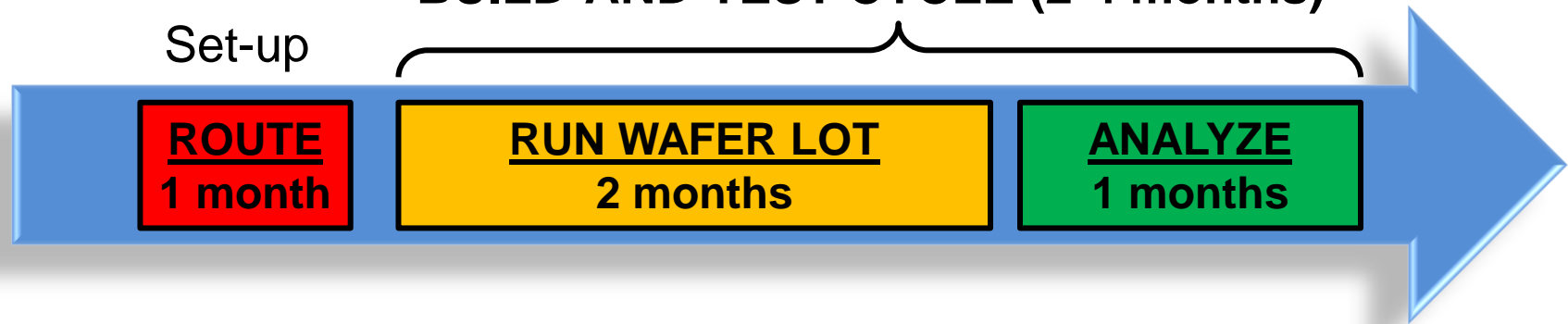


Quantify sensitivity of structure  
CDs to process parameters

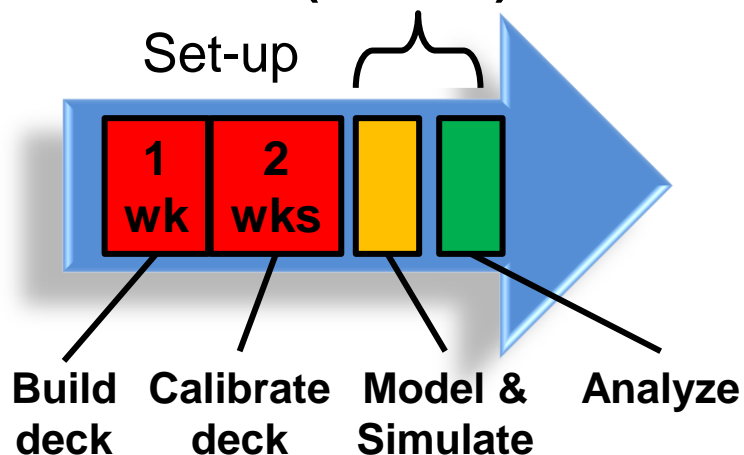
# Virtual Fabrication vs. “Build and Test”

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## BUILD-AND-TEST CYCLE (2-4 months)



## VIRTUAL CYCLE (1 week)



### Benefits:

- Faster time to production
- More experiments → higher yield
- Lower development cost



# Virtual Fabrication for MEMS Foundries

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## MEMS foundries use SEMulator3D for:

- **Process development:** Predict and diagnose process issues and improve yield
- **Physical design verification:** Verify structures, release and electrical continuity before tape out
- **Customer support:** communicate process and design and information with customers
- **Failure analysis**



**DALSA**

*"SEMulator3D gives engineers the ability to do virtual test runs to verify that a device design is compatible with the manufacturing process, and that the 3D result is as expected. Design mistakes and shortcomings can be identified, even if they are compatible with 2D layout rules."*

**X FAB**  
MIXED-SIGNAL FOUNDRY EXPERTS

*"The benefits of visualizing accurate 3-D virtual MEMS prototypes include increased probability of achieving first-time success by minimizing analysis errors, increased design efficiency by identifying process errors early, avoiding undesired effects that would have reduced yield, and more efficient communication between design engineers and outside groups."*

# In Conclusion:

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## Most MEMS industry leaders are Coventor customers

- IDMs, Fabless, Foundries, R&D Organizations, Universities

## Coventor's unique product platform speeds time to market

- **MEMS+** enables rapid design exploration, optimization, and automated hand-off between MEMS and IC designers
- **CoventorWare** for specialized coupled physics challenges
- **SEMulator3D** for process development and sign-off

## Coventor is well positioned to enable industry trends

- Continued growth from mobile and consumer applications
- New devices and new applications (passive displays, IR imaging,...)
- Growth of the Fabless/Independent Foundry business model